

INFORMATION DISCLOSURE CITATION PTO-1449		ATTY. DOCKET NO. NTA-019-5-10		SERIAL NO. 10/688559 Filed Herewith		
		APPLICANT Pierrat, et al.				
		FILING DATE Filed Herewith 10/16/03		GROUP 2825		
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
PD	4,231,811	11/4/80	Somekh, et al.	148	1.5	9/13/79
	4,456,371	6/26/84	Lin	355	71	6/30/82
	4,902,899	2/20/90	Lin, et al.	250	492.1	6/1/87
	5,498,579	3/12/96	Borodovsky, et al.	437	250	6/8/94
	5,553,274	9/3/96	Liebmman	395	500	6/6/95
	5,636,002	6/3/97	Garofalo	355	53	10/31/95
	5,663,017	9/2/97	Schinella, et al.	430	5	6/7/95
	5,723,233	3/3/98	Garza, et al.	430	5	2/27/96
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	5,821,014	10/13/98	Chen, et al.	430	5	2/28/97
	5,862,058	1/19/99	Samuels, et al.	364	491	5/16/96
	5,879,844	3/9/99	Yamamoto, et al.	430	30	12/20/96
	5,885,734	3/23/99	Pierrat, et al.	430	5	8/15/96
	5,900,338	5/4/99	Garza, et al.	430	5	8/15/97
	5,994,002	11/30/99	Matsuyoka	430	5	9/4/97
	6,004,702	12/21/99	Lin	430	5	5/21/98
	6,077,310	6/20/00	Yamamoto, et al.	716	19	1/29/99
PD	6,078,738	6/20/00	Garza, et al.	395	500.22	5/8/97
EXAMINER	Paul Dinh		DATE CONSIDERED		2/21/06	

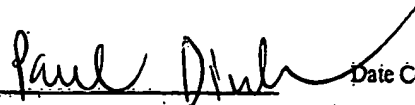
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U.S. PATENT DOCUMENTS						
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PD	4,426,584	1/17/1984	Bohlen, et al.	250	492.2	6/3/1981
	4,895,780	1/23/1990	Nissah-Cohen, et al.	430	5	10/25/1988
	5,208,124	5/4/1993	Sporon-Fiedler, et al.	430	5	3/19/1991
	5,682,323	10/28/1997	Pasch, et al.	364	491	3/6/1995
	5,958,635	9/28/1999	Reich, et al.	430	30	10/20/1997
	5,972,541	10/26/1999	Sugawara, et al.	430	5	3/4/1998
	6,007,310	12/28/1999	Jacobsen, et al.	417	362	5/23/1997
	6,114,071	9/5/2000	Chen, et al.	430	5	4/6/1998
	6,289,499	9/11/2001	Rieger, et al.	716	21	1/7/2000
	6,249,597 B1	6/19/2001	Tsujaka	382	144	12/17/1998

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U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
PD	6,014,456	1/11/2000	Tsudaka	382	144	7/15/1996
	6,154,563	11/28/2000	Tsudaka	382	144	12/17/1998
	6,298,473 B1	10/2/2001	Ono, et al.	716	21	12/3/1998
	6,453,457 B1	9/17/2002	Pierrat, et al.	716	19	9/29/2000
PD	2002/0100004 A1	7/25/2002	Pierrat, et al.	716	5	3/15/2002

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Paul Rink

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	Filed Herewith	

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PD	5,991,006	11/23/0199	Tsudaka	355	53	10/27/1997
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	5,663,893	09-1997	Wampler et al.	716	19
	6,416,907	07-2002	Winder et al.	430	5
	6,453,457	09-2002	Pierrat et al.	716	19
PD	6,523,162	02-2003	Agrawal et al.	716	19

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Paul Pierrat

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FOREIGN PATENT DOCUMENTS							
Ref ID	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
00076	WO 00/67074 A1	11/9/2000	WO	—	—	<input type="checkbox"/>	<input type="checkbox"/>
00077	WO 00/67075 A1	11/9/2000	WO	—	—	<input type="checkbox"/>	<input type="checkbox"/>
00078	WO 00/67076 A1	11/9/2000	WO	—	—	<input type="checkbox"/>	<input type="checkbox"/>

INFORMATION DISCLOSURE CITATION PTO-1449		ATTY. DOCKET NO.: NTI-019-5-1D		SERIAL NO. 10/688559 Filed Herewith			
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FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
PD	3-210560	9/13/91	JP			<input type="checkbox"/>	<input type="checkbox"/>
	8-236317	9/6/96	JP			<input type="checkbox"/>	<input type="checkbox"/>
	10-133356	5/22/98	JP			<input type="checkbox"/>	<input type="checkbox"/>
	11-143085	5/28/99	JP			<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
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						<input type="checkbox"/>	<input type="checkbox"/>
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EXAMINER	Paul D. White		DATE CONSIDERED		2/21/06		

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		Applicant PIERRAT, Christophe		Filing Date 10/16/93 Group 2825 Filed Herewith			
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
PD	3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
	2,324,169 A	10/14/1998	GB			<input type="checkbox"/>	<input type="checkbox"/>
PD	WO 99/47981	9/23/1999	WU			<input type="checkbox"/>	<input type="checkbox"/>

EXAMINER:

Paul Vinh

Date Considered:

2/21/06

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		NTI-019-5-10	Filed Herewith
		Applicant	10/688559
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		10/16/03	2825
		Filed Herewith	
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00082	Barouch, E., et al., "OPTIMASK: An OPC Algorithm for Chrome and Phase-Shift Mask Design", SPIE, Vol. 2440, pp. 192-206, February 1995.		
00084	Brunner, T., et al., "Approximate Models for Resist Processing Effects", SPIE, Vol. 2726, pp. 198-207, March 1996.		
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00086	Casey, Jr., J.D., et al., "Chemically Enhanced FLB Repair of Opaque Defects on Molybdenum Silicide Photomasks", SPIE, Vol. 3236, pp. 487-497 (1997).		
00087	Chang, K., et al., "Accurate Modeling of Deep Submicron Interconnect Technology", TMA Times, Vol. IX, No. 3 (1997).		
00094	Gans, F., et al., "Printability and Repair Techniques for DUV Photomasks", SPIE, Proceedings Of The 17th Annual Symposium On Photomask Technology And Management, Vol. 3236, pp. 136-141 (1997).		
00099	Ham, Y.M., et al., "Dependence of Defects in Optical Lithography", Jpn. J. Appl. Phys., Vol. 31, pp. 4137-4142 (1992).		
00101	Henke, W., et al., "A Study of Reticle Defects Imaged Into Three-Dimensional Developed Profiles of Positive Photoresist Using the Solid Lithography Simulator", Microelectronics Eng., Vol. 14, pp. 283-297 (1991).		
00102	Ibsen, K., et al., "Clear Field Reticle Defect Disposition for Advanced Sub-Half Micron Lithography", SPIE, Proceedings Of The 17th Annual Symposium On Photomask Technology And Management, Vol. 3236, pp. 124-135 (1997).		
00105	Ishiwata, N., et al., "Novel Alternating Phase Shift Mask with Improved Phase Accuracy", SPIE, Proceedings Of The 17th Annual Symposium On Photomask Technology And Management, Vol. 3236, pp. 243-249 (1997).		
00106	Jinbo, H., et al., "0.2um or Less i-Line Lithography by Phase-Shifting-Mask Technology", IEEE, pp. 33.3.1-33.3.4 (1990).		
00107	Jinbo, H., et al., "Application of Blind Method to Phase-Shifting Lithography", IEEE, 1992 Symposium On VLSI Technology Digest Of Technical Papers, pp. 112-113 (1992).		
00108	Jinbo, H., et al., "Improvement of Phase-Shifter Edge Line Mask Method", Japanese Journal Of Applied Physics, Vol. 30, No. 11B, pp. 2998-3003, November 1991.		
00109	Karklin, L., "A Comprehensive Simulation Study of the Photomask Defects Printability", SPIE, Vol. 2621, pp. 490-504 (1995).		

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00110	Kimura, T., et al., "Subhalf-Micron Gate GaAs Mesfet Process Using Phase-Shifting-Mask Technology", IEEE, GaAs IC Symposium, pp. 281-284 (1991).		
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00123	Ohtsuka, H., et al., "Phase Defect Repair Method for Alternating Phase Shift Masks Conjugate Twin-Shift Method", Jpn. J. Appl. Phys., Vol. 31, pp. 4143-4149 (1992).		
00124	Park, C., et al., "An Automatic Gate CD Control for a Full Chip Scale SRAM Device", SPIE, Vol. 3236, pp. 350-357 (1997).		
00125	Pai, Y.C., et al., "Exploiting Structure in Fast Aerial Image Computation for Integrated Circuit Patterns", IEEE Transactions On Semiconductor Manufacturing, Vol. 10, No. 1, pp. 62-74, February 1997.		
00126	Pai, Y.C., et al., "Phase-Shifting Masks for Microlithography: Automated Design and Mask Requirements", J. Opt. Soc. Am., Vol. 11, No. 9, pp. 2438-2452, September 1994.		
00128	Precim, "Proxima System", Precim Company, Portland, Oregon (2 pages). (Date not available)		
00129	Precim, "Proxima Wafer Proximity Correction System", Precim Company, Portland, Oregon (2 pages). (Date not available)		
00130	Kieger, M., et al., "Customizing Proximity Correction for Process-Specific Objectives", SPIE, Vol. 2726, pp. 651-659 (1996).		
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		Applicant	10/68559
		PIERRAT, Christophe	
		Filing Date 10/16/03	Group 2825
		Filed Herewith	
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Ref ID	CITATION		
00132	Rieger, M.; et al., "System for Lithography Proximity Compensation", Precim Company, Portland, Oregon, September 1993 (28 pages).		
00133	Rieger, M., et al., "Using Behavior Modeling for Proximity Correction", Precim Company, Portland, Oregon (6 pages). (Date not available)		
00134	Roman, B., et al., "Implications of Device Processing on Photomask CD Requirements", SPIE, Vol. 3236 (1997) (Abstract Only).		
00136	Spence, C., et al., "Automated Determination of CAD Layout Failures Through Focus: Experiment and Simulation", SPIE, Vol. 2197, pp. 302-313 (1994).		
00137	Spence, C., et al., "Detection of 60(degree) Phase Defects on Alternating PSMs", Advanced Micro Devices, KLA-Tencor, DuPont RTC (2 pages). (Date not available)		
00140	Stimman, J., et al., "Fast Proximity Correction with Zone Sampling", SPIE, Vol. 2197, pp. 294-301 (1994).		
00141	Stimman, J., et al., "Optimizing Proximity Correction for Wafer Fabrication Processes", SPIE, Photomask Technology And Management, Vol. 2322, pp. 239-246 (1994).		
00142	Stimman, J., et al., "Spatial Filter Models to Describe IC Lithographic Behavior", Precim Corporation, Portland, Oregon (10 pages). (Date not available)		
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00144	Sugawara, M., et al., "Defect Printability Study of Attenuated Phase-Shifting Masks for Specifying Inspection Sensitivity", Sony Corporation, Kanagawa, Japan (16 pages). (Date not available)		
00146	Trans Vector, "Now Better Quality Photomasks", Trans Vector Technologies, Inc., Camarillo, California (4 pages). (Date not available)		
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00150	Wiley, J., et al., "Device Yield and Reliability by Specification of Mask Defects", Solid State Technology, Vol. 36, No. 7, pp. 65-66, 70, 72, 74, 77, July 1993.		
00151	Wiley, J., et al., "The Effect of Off-Axis Illumination on the Printability of Opaque and Transparent Reticle Defects", SPIE, Vol. 2512, pp. 432-440 (1995).		
00152	Wiley, J., et al., "Phase Shift Mask Pattern Accuracy Requirements and Inspection Technology", SPIE, Integrated Circuit Metrology, Inspection, And Process Control V, Vol. 1464, pp. 346-355 (1991).		
00153	Yen, A., et al., "Characterization and Correction of Optical Proximity Effects in Deep-Ultraviolet Lithography Using Behavior Modeling", J. Vac. Sci. Technol. B, Vol. 14, No. 6, pp. 4175-4178, November/December 1996.		
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PD	Ackmann, P. et al., "Phase Shifting And Optical Proximity Corrections To Improve CD Control On Logic Devices In Manufacturing For Sub 0.35 μ m I-Line", Advance Micro Devices (8 pages). (Date not available)	
1	Asai, N. et al., "Proposal For The Coma Aberration Dependent Overlay Error Compensation Technology", <i>Jpn. J. Appl. Phys.</i> , Vol. 37, pp. 6718-6722 (1998).	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
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PD	Spence, C. et al., "Integration Of Optical Proximity Correction Strategies In Strong Phase Shifters Design For Poly-Gate Layers", <i>Bacus News</i> , Vol. 15, Issue 12, pp. 1, 4-13, December 1999.	
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EXAMINER'S INITIALS	CITATION		
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EXAMINER:

Paul Dineen

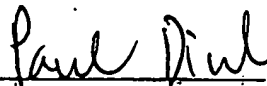
Date Considered:

2/21/06

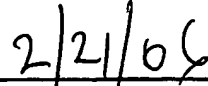
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No. NTI-019-5-1D Applicant PIERRAT, Christophe Filing Date 10/16/03 Group 2825 Filed Herewith	Serial No. 10/688559 Filed Herewith
	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
EXAMINER'S INITIALS	CITATION	
PD	Balasinski, A., et al., "Comparison of Mask Writing Tools and Mask Simulations for 0.16um Devices", IEEE, SEMI Advanced Semiconductor Manufacturing Conference, pp. 372-377 (1999).	

EXAMINER:



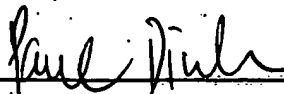
Date Considered:



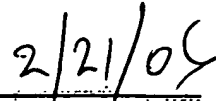
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPFP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No. NTI-019-S-1D	Serial No. 10/688559
		Applicant PIERRAT, Christophe	Filed Herewith
		Filing Date 10/16/03	Group 2825
		Filed Herewith	
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
EXAMINER'S INITIALS	CITATION		
PD	Chuang, H., et al., "Practical Applications of 2-D Optical Proximity Corrections for Enhanced Performance of 0.25um Random Logic Devices", IEEE, pp. 18.7.1-18.7.4, December 1997.		

EXAMINER:



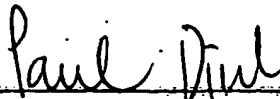
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INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No. NTI-019-5-10	Serial No. 10/688559
		Applicant PIERRAT, Christophe	Filed Herewith Group 2825
Filing Date 10/16/03			
Filed Herewith			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
EXAMINER'S INITIALS	CITATION		
PD	Cobb, N., et al., "Fast, Low-Complexity Mask Design", SPIE, Vol. 2440, pp. 313-327, February 22-24, 1995.		
	Cobb, N., et al., "Experimental Results on Optical Proximity Correction With Variable Threshold Resist Model", SPIE, Vol. 3051, pp. 458-468, March 12-14, 1997.		
	Cobb, N., "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing", Dissertation, University of California at Berkeley, UMI Microform 9907038 (139 pages). (Date not available)		
PD	Toubian, O., et al., "Phase Aware Proximity Correction for Advanced Masks", SPIE, Vol. 4000, pp. 160-170, March 1-3, 2000.		

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Date Considered:

2/21/06

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